

In the Specification:

Please amend the second paragraph on page 9, line 14 as follows:

An organic planarizing coating 118, e.g., an antireflective coating (ARC), can be deposited. The organic planarizing coating can be planarized 119. A reactive ion etch (RIE) of the coating layer, e.g., with a selectivity of 1:1 (organic coating to oxide), selective to polysilicon, can be performed to open the polysilicon stud 120, wherein the polysilicon in the support is high enough to clear the top oxide. Alternatively, a second ES mask can be used to remove the oxide on the polysilicon.